

[54] **PHOTOSENSITIVE RESIN COMPOSITION
CONTAINING PULLULAN OR ESTERS
THEREOF**

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[22] Filed: **Nov. 5, 1974**

[21] Appl. No.: **521,151**

[30] **Foreign Application Priority Data**

Nov. 12, 1973 Japan..... 48-127505

Nov. 12, 1973 Japan..... 48-127506

[52] **U.S. Cl.**..... **204/159.12; 96/35.1; 96/36.3; 204/160.1; 200/17.4 R; 200/17.4 G; 200/17.4 C; 260/209 R; 260/234 R; 427/54**

[51] **Int. Cl.²**..... **C08L 1/00; C08L 3/00**

[58] **Field of Search**..... **96/35.1; 260/234; 204/160.1, 159.12, 159.23, 159.24, 159.15, 159.16**

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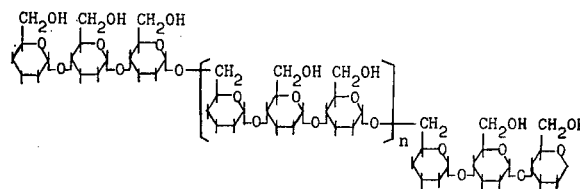
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[57] **ABSTRACT**

A photosensitive resin composition comprising pullulan, which is a polymer having repetition units of maltotriose and is represented by the formula,



wherein n is an integer of 20 to 8,000, and/or a derivative thereof, a photopolymerizable monomer, a photosensitizer and a thermal polymerization inhibitor, or comprising the said pullulan, which has been incorporated with a photoactive reaction group to provide photosensitivity, and a photosensitizer, is a novel composition low in viscosity which can be prepared by use of water and can be formed into a photosensitive plate capable of being developed with water to give a clear image. Since the pullulan in said composition has no toxicity, the waste water formed at the time of development of said photosensitive plate can be treated with ease.

21 Claims, No Drawings